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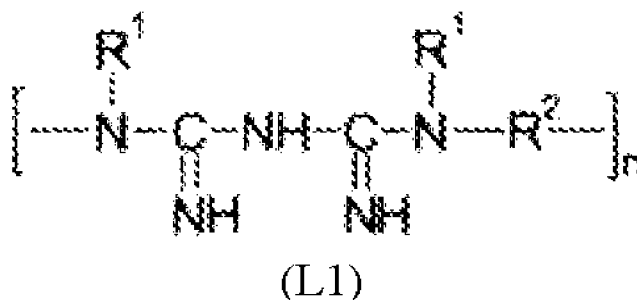
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(54) Title: COMPOSITION FOR METAL ELECTROPLATING COMPRISING LEVELING AGENT



(57) Abstract: Disclosed is a composition comprising a source of metal ions, one or more suppressing agents and at least one additive comprising a linear or branched, polymeric biguanide compound comprising the structural unit of formula L1 or the corresponding salt thereof, wherein R<sup>1</sup> is independently selected from H or an organic radical having 1-20 carbon atoms; R<sup>2</sup> is an divalent organic radical having 1-20 carbon atoms, optionally comprising 20 polymeric biguanide side branches; and n is an integer of 2 or more.